Special Issue

Advancements in Optical Measurement Devices and Technologies: 2nd Edition

Message from the Guest Editors

Following the success of the Special Issue "Advancements in Optical Measurement Devices and Technologies" for the journal *Metrology*, we propose its second edition. Optical measurement techniques are now widespread and indispensable for various scientific and industrial applications. Their metrological characterization is becoming increasingly important, as are all aspects related to measurement methods. In parallel, the integration of artificial intelligence (AI) and machine learning (ML) is transforming measurement science by enabling enhanced data analysis, intelligent sensing, automated calibration and improved uncertainty estimation. This Special Issue aims to gather cutting-edge research and developments in this dynamic field, exploring novel optical measurement devices and sensing techniques, their applications and their metrological characterization, including the growing role of AI-driven approaches.

Guest Editors

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Deadline for manuscript submissions

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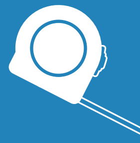

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About the Journal

Message from the Editor-in-Chief

Metrology draws together researchers from diverse areas of metrology or measurement technology in a wide variety of applications. I encourage you to submit your manuscripts for consideration or publication in the area of measurement engineering, according to the scope of the journal. *Metrology* is supported by our authors and their institutes through low article processing charges (APC) for accepted papers. We hope you will support the journal by becoming one of our authors.

Editor-in-Chief

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